

SEMICONDUCTOR FILM COMPOSITION, METHOD OF MANUFACTURING
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SEMICONDUCTOR MEMBER, METHOD OF MANUFACTURING SEMICONDUCTOR
PROCESSING MATERIAL, AND SEMICONDUCTOR DEVICE

ABSTRACT

A semiconductor film composition including: a compound (A) including a cationic functional group containing at least one of a primary nitrogen atom or a secondary nitrogen atom and having a weight average molecular weight of from 10,000 to 400,000; a crosslinking agent (B) which includes the three or more $-C(=O)OX$ groups (X is a hydrogen atom or an alkyl group having from 1 to 6 carbon atoms) in the molecule, in which from one to six of three or more $-C(=O)OX$ groups are $-C(=O)OH$ groups, and which has a weight average molecular weight of from 200 to 600; and water (D), in which the compound (A) is an aliphatic amine.